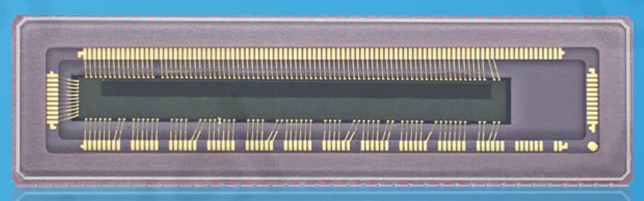


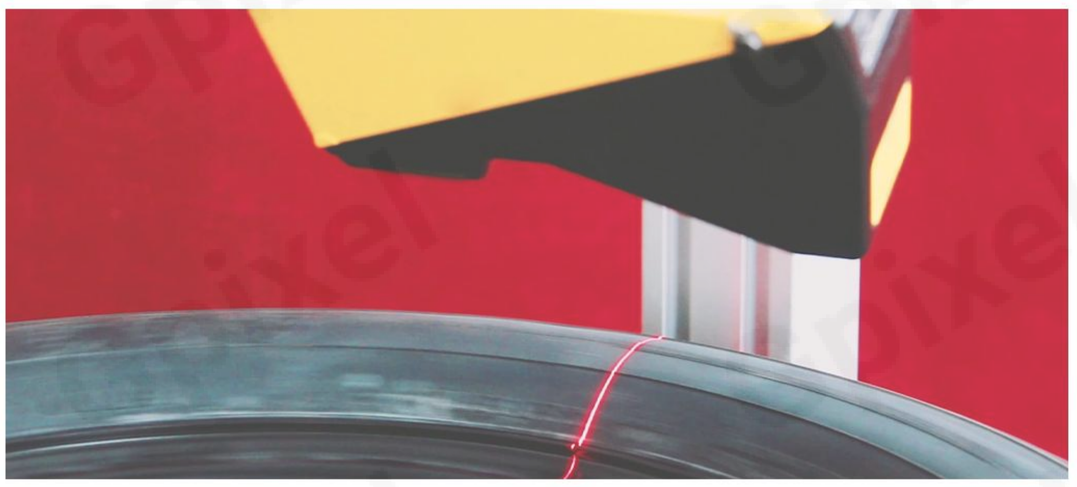
GLR1202BSI-L

2K 12.5 µm x 1000 µm PIXEL SIZE
High Speed BSI LINE SCAN CMOS IMAGE SENSOR

GLR1202BSI-L features a large rectangular pixel size of 12.5 µm (H) × 1000 µm (V) and a resolution of 2000 × 1 pixels. Manufactured using advanced BSI wafer processing, it achieves a quantum efficiency of nearly 90% at 650 nm. Sensor offers high FWC of 2 Me^- with high dynamic range of 69 dB. User can also switch to High Gain mode to achieve lower noise based on application demand.

In addition, sensor supports on-chip 1 × 2 binning, doubling the sensitivity with higher line rate of 350 kHz.

GLR1202BSI-L is packaged in a CLCC housing with double-sided anti-reflection coated glass.



Key Features and Benefits

- Pixel Size：12.5 µm x 1000 µm
- Fast Line Rate：240 kHz
- High QE
- 1x2 Binning

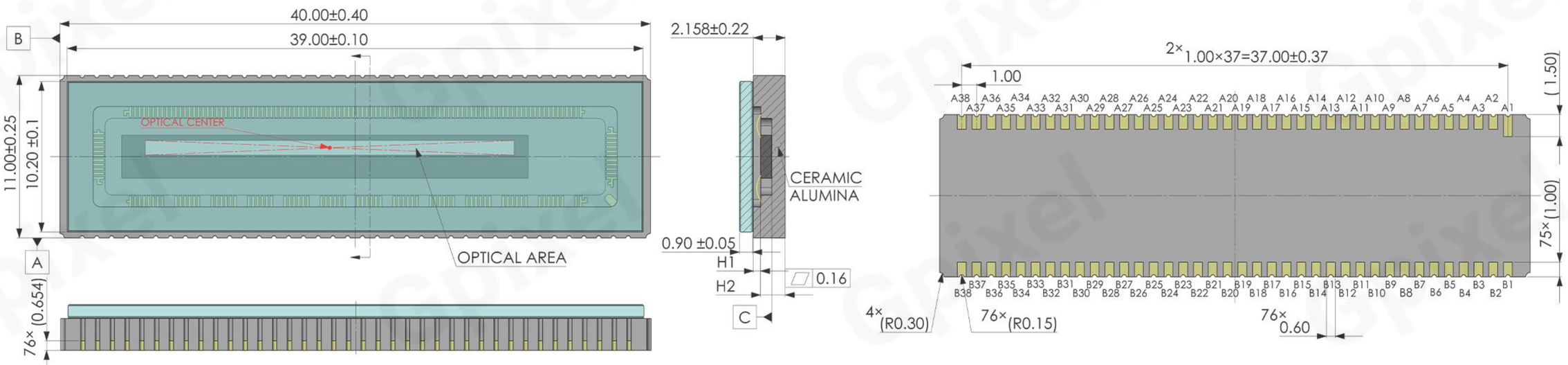
Applications

- Automation&Inspection
- Metrology
- Spectroscopy

Specifications

Nr of Active Pixels	2000 (H) x 1 (V)	Optical Format	25 mm
Pixel Size	12.5 µm x 1000 µm	Shutter Type	Global Shutter
Peak QE	91 % (440 nm)	Temporal Noise	675 e^- (LG) 215 e^- (HG)
Max. SNR	63 dB	Dynamic Range	69 dB (LG) 58 dB (HG)
Max Line Rate	240 kHz 350 kHz (1x2 binning)	Dark Current	T.B.D
Output Format	5x Sub-LVDS	Max. Data Rate	6 Gbps
Chroma	Mono	Power Consumption	< 500 mW
Supply Voltage	3.3 V (Analog) 1.5 V (Digital) 1.8 V (IO)	Package	76 pins CLCC (40 mm x 11 mm)

Package Drawing



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